## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**Applicants** 

Noriaki MATSUNAGA et al.

U.S. Serial No.

Not Yet Assigned

Filing Date

July 28, 2003

For

SEMICONDUCTOR DEVICE AND ITS MANUFACTURING

**METHOD** 

Group Art Unit

Not Yet Assigned

745 Fifth Avenue

New York, New York 10151

**EXPRESS MAIL** 

Mailing Label Number:

EV205872328US

Date of Deposit:

July 28, 2003

I hereby certify that this paper or fee is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" Service under 37 CFR 1.10 on the date indicated above and is addressed to: Mail Stop Patent Application, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

(Typed or printed name of person mailing paper or fee)

(Signature of person mailing paper or fee)

## INFORMATION DISCLOSURE STATEMENT

Mail Stop Patent Application Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

The Examiner's attention is respectfully invited to review the following enclosed and listed document which is also listed on the accompanying Form PTO-1449, enclosed in duplicate.

## **OTHER REFERENCES**

1. K. Higashi, et al., "A Manufacturable Copper/Low-k SiOC/SiCN Process Technology for 90nm-node High Performance eDRAM," PROCEEDINGS OF THE 2002 INTERNATIONAL INTERCONNECT TECHNOLOGY CONFERENCE, June 2002, pp. 15-17.

## REMARKS

Pursuant to Rule 37 C.F.R. §1.97(b)(3), an Information Disclosure Statement shall be considered by the Patent Office filed before the mailing date of a first Office Action on the merits.

This Information Disclosure Statement is not a representation that the document cited herein is considered most pertinent, or that a search has been undertaken, or that the cited document is indeed prior art. The Examiner is invited to undertake an independent search.

Applicants assert that the claimed invention is patentable over this document.

Applicants respectfully request that the Examiner consider and make of record the document cited herein and that a copy of Form PTO-1449, appropriately initialed by the Examiner, be returned to Applicants' attorney.

It is believed no fee is due, however, the Examiner is authorized to charge any deficit or credit any overpayment to Deposit Account No. 50-0320.

Respectfully submitted,

FROMMER LAWRENCE & HAUG LLP Attorneys for Applicants

By:

Registration No. 39,440 Tel. (212) 588-0800 Fax (212) 588-0500

										Sheet 1 of 1
Based on Form PTO-1449 (3/90)						ATTY. DOCKET NO.		SERIAL NO.		
						790001-203	Not Yet Assigned			
LIST OF REFERENCES CITED BY APPLICANT						APPLICANTS				
(Use several sheets if necessary)						Noriaki MATSUNAGA et al.				
						FILING DATE	GROUP			
						July 28, 200	Not Yet Assigned			
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL		DOCUMENT NUMBER		DATE	NAME		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
						<del></del>			<del></del>	
								<del> </del>		
FOREIGN PATENT DOCUMENTS										
		DOCUMENT NUMBER DATE			CLOIV II	COUNTRY CLASS		SUBCLASS TRANS		SLATION
'		Doomen't nomber		22					YES	NO
	·						<del></del>	<del>                                     </del>		
						<del></del>	,			
				1					<del>                                     </del>	
							<del></del>	<del> </del>	<u> </u>	
									<del> </del>	
									<u> L</u>	L
						Author, Title, Date, Pertinent F				
		K. Higashi, et al., "A Manufacturable Copper/Low-k SiOC/SiCN Process Technology for 90nm-node High Performa eDRAM," PROCEEDINGS OF THE IEEE 2002 INTERNATIONAL INTERCONNECT TECHNOLOGY CONFERENCE, June 2002, pp 15-17.								erformance 1002, pp.
				<del></del>						
	EXAMINER									
	l	L	L <u> </u>	<del></del>		DATE CONSIDERED	<del></del>			
• EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.										